

Scanning Thermal Microscopy of functional layers used in halide perovskite devices

Ralf Heiderhoff

CM@S School of Electrical, Information and Media Engineering
Institute of Electronic Devices

Summer School Khiva | May 2023

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Introduction

University of Wuppertal



- since 1863 School of Engineering
- 1972 Foundation of BU Wuppertal
- 8 Faculties
- 24,000 Students



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Introduction

Prof. Dr. Thomas Riedl

Organic / Hybrid Photovoltaics

Metaloxide Semiconductors and Electrodes

Reliability & Permeation Barrier Technology

Light Emitting Devices

Centers of interest in research and development:

- Scanning Electron Microscopy (SEM),
- different measurement set-ups of Scanning Probe Microscopy (SPM) (like Optical Near-field (SNOM), Tunneling (STM), or Scanning Force Microscopy (SFM))

as well as their combination to hybrid systems.

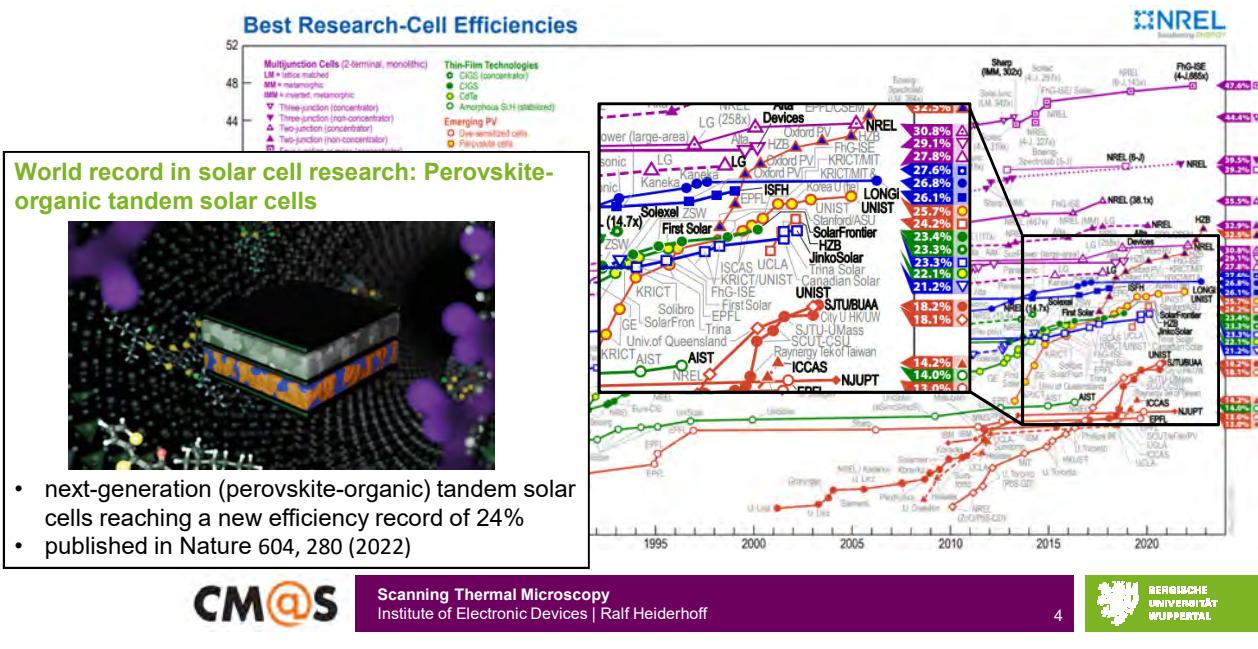
650 m² lab space (230 m² clean room)

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Motivation and Purpose



Motivation and Purpose

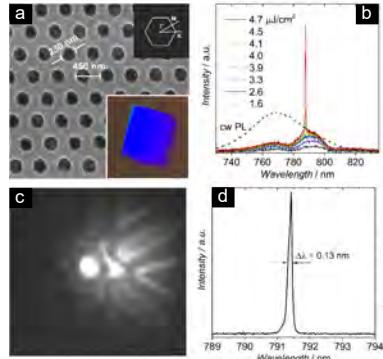
ADVANCED SCIENCE NEWS
www.advancesciencenews.com

MAPbI₃



Photonic Nanostructures Patterned by Thermal Nanoimprint Directly into Organo-Metal Halide Perovskites

Neda Pourdavoud, Si Wang, André Mayer, Ting Hu, Yiwang Chen, André Marianovich, Wolfgang Kowalsky, Ralf Heiderhoff, Hella-Christin Scheer, and Thomas Riedl*



Pourdavoud et al. *Adv. Mater.* 29, 1605003 (2017)

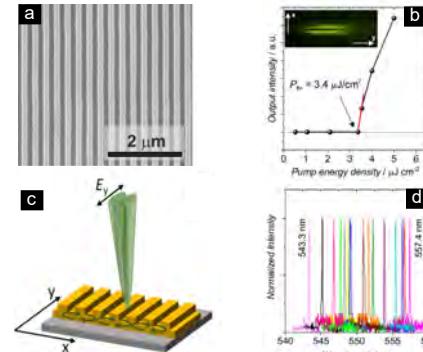
COMMUNICATION
Perovskite Lasers

MAPbBr₃

ADVANCED TECHNOLOGIES
www.advantechol.de

Distributed Feedback Lasers Based on MAPbBr₃

Neda Pourdavoud, André Mayer, Maximilian Buchmüller, Kai Brinkmann, Tobias Häger, Ting Hu, Ralf Heiderhoff, Ivan Shutsko, Patrick Görn, Yiwang Chen, Hella-Christin Scheer, and Thomas Riedl*



Pourdavoud et al. *Adv. Mater. Technol.* 3, 1700253 (2018)

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Motivation and Purpose

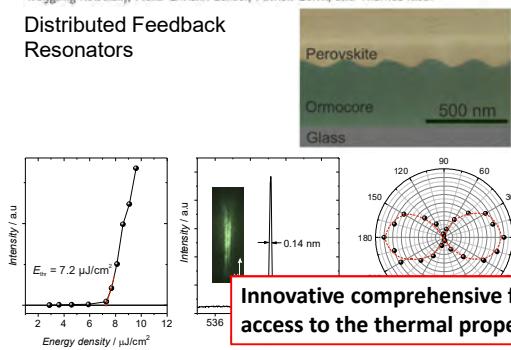
COMMUNICATION
Perovskite Lasers

ADVANCED MATERIALS
www.admatz.de

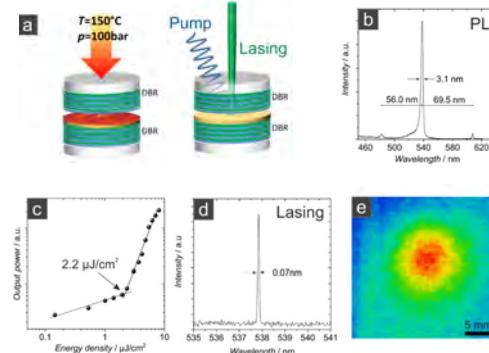
Room-Temperature Stimulated Emission and Lasing in Recrystallized Cesium Lead Bromide Perovskite Thin Films

Neda Pourdavoud, Tobias Häger, André Mayer, Piotr Jacek Cegielski, Anna Lena Giesecke, Ralf Heiderhoff, Selina Olthof, Stefan Zaefferer, Ivan Shutsko, Andreas Henkel, David Becker-Koch, Markus Stein, Marko Gheorghici, Ouacef Chorfi, Hans-Hermann Johannes, Detlef Rogalla, Max Christian Lemme, Martin Koch, Yana Vaynsht, Klaus Meerholz, Wolfgang Kowalsky, Hella-Christin Scheer, Patrick Görn, and Thomas Riedl*

Distributed Feedback Resonators



Vertical Cavity Surface Emitting Laser



Innovative comprehensive failure and reliability investigations are mandatory to get access to the thermal properties of these devices and systems as a whole!

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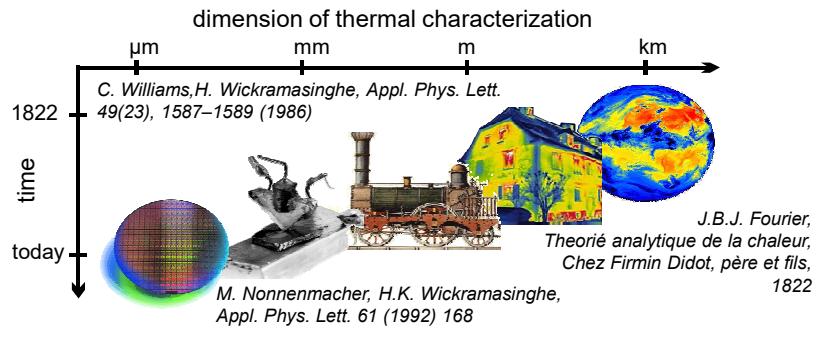
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Motivation



Fourier law $\vec{q} = -\vec{\lambda} \cdot \text{grad } T(\vec{r})$

general equation of heat conduction $\rho c \frac{\partial T(\vec{r})}{\partial t} = \frac{\partial}{\partial x} \left(\lambda_x \frac{\partial T(\vec{r})}{\partial x} \right) + \frac{\partial}{\partial y} \left(\lambda_y \frac{\partial T(\vec{r})}{\partial y} \right) + \frac{\partial}{\partial z} \left(\lambda_z \frac{\partial T(\vec{r})}{\partial z} \right) + q_E$

ρ : specific density q_E : amount of heat generated per unit time and unit volume

A. Freeman, *Theory of heat*, Cambridge University Press, London, 1878



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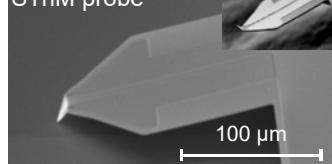


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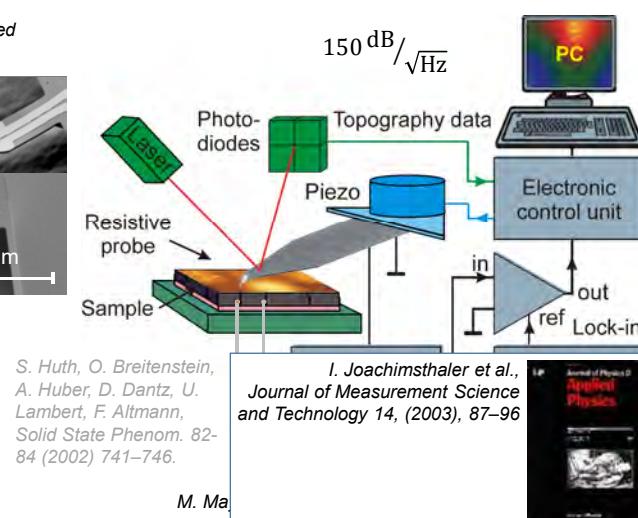
Set-up of Scanning Thermal Microscope

P. Tovee et al., *Journal of Applied Physics*, (2012) 112, 114317

commercially available SThM probe



Dinwiddie R B, et al.;
Thermal Conductivity
(1994) 22, 668



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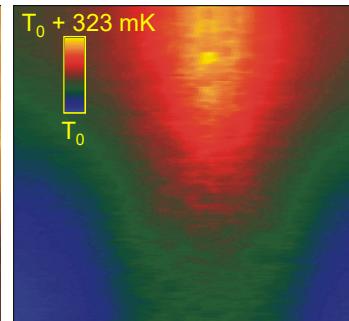
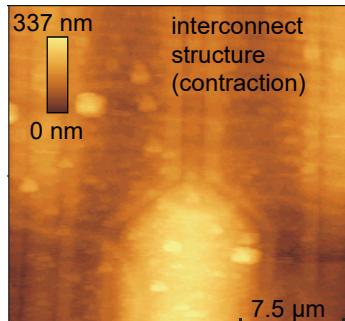


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Measurements of temperature distributions

Voltage source:
local heat
dissipation in
dependence on
the heating power
density

G.B.M. Fiege et al.
Microelectron. Reliab.
38 (1998) 957–961.



5 $\frac{mK}{\sqrt{Hz}}$: thermal noise

$\frac{\Delta x}{\Delta T}$: 1/temperature gradient

30 nm: effect. contact area in air

achievable spatial resolution:

$$\Delta x = 5 \frac{mK}{\sqrt{\Delta f}} \cdot \sqrt{\Delta f} \frac{\Delta x}{\Delta T} + 30 \text{ nm}$$

10 nm: in ultra high vaccuum
W. Jeong et al., *Sci.Rep.4* (2014) 4975

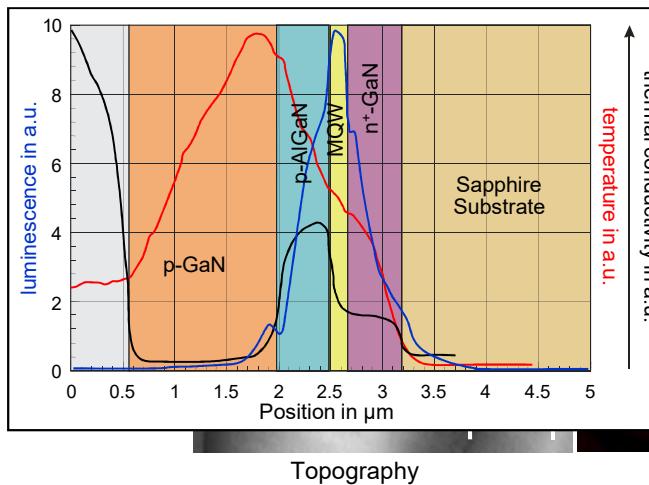


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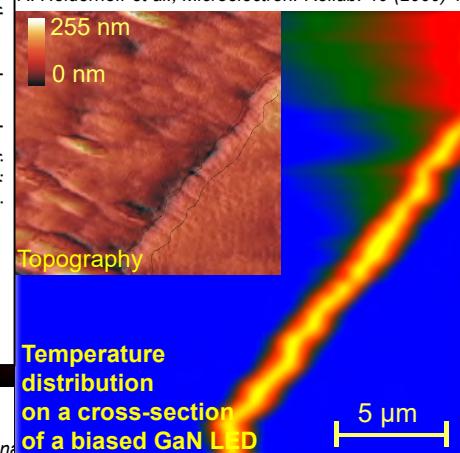
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Reliability investigations by means of SThM



R. Heiderhoff et al., *Microelectron. Reliab.* 40 (2000) 1383–1388



M. Palaniappan et al., *Proc. 25th Int. Symp. Test. Fail. Anal.*

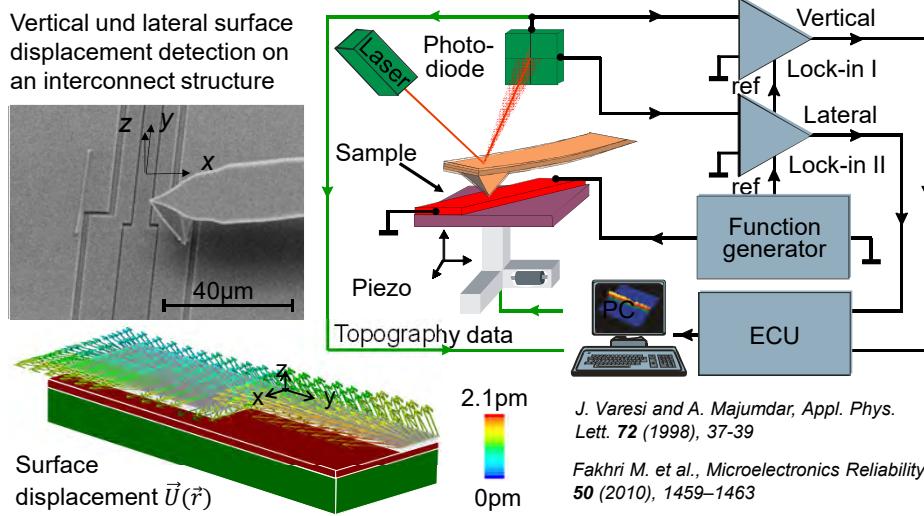


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Scanning Joule Expansion Microscopy



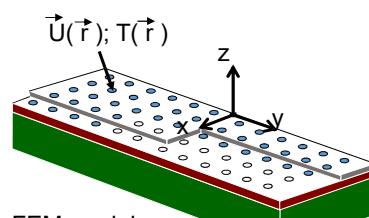
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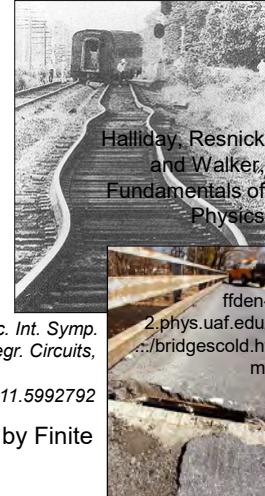
Thermally induced mechanical stress analysis

Electric current → Thermally induced mechanical stress



M. Fakhri et al., *Proc. Int. Symp. Phys. Fail. Anal. Integr. Circuits, IPFA*. (2011).
 doi:10.1109/IPFA.2011.5992792

Solution of thermal and thermo-elastic differential equations by Finite Element Method and using experimental data as boundary conditions

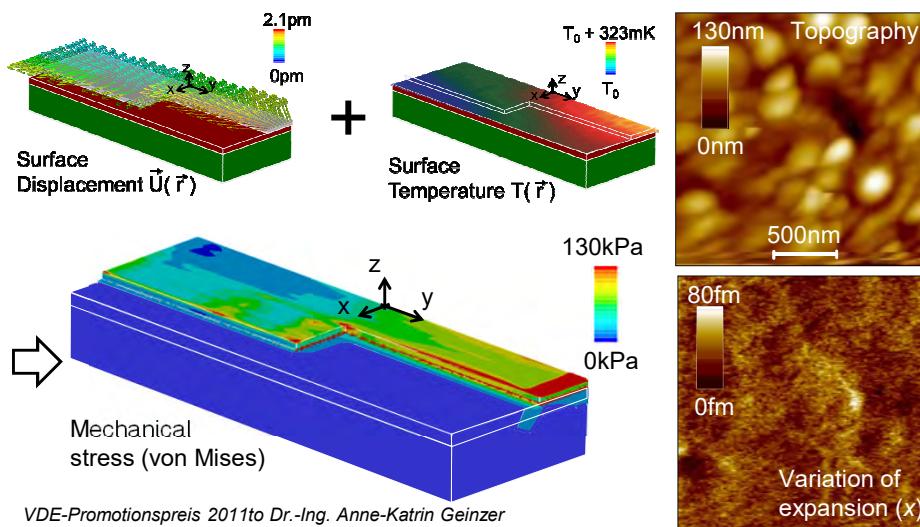


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Thermally induced mechanical stress analysis

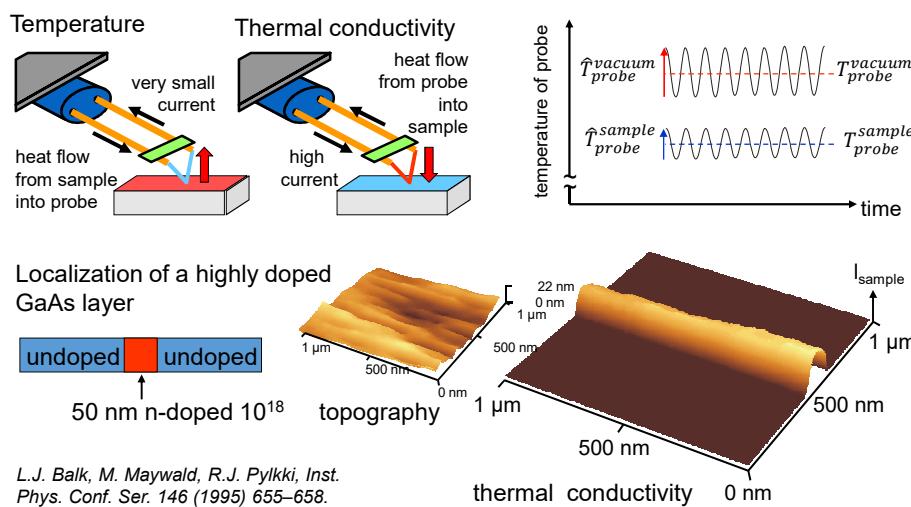


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Heat flows in Scanning Thermal Microscopy



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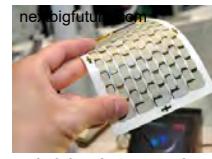
Motivation and Purpose



thin film batteries



flexible solar cells



bendable thermoelectrics

Performances/efficiencies are significantly influenced by thermal properties
(reliability, life time, thermoelectric figure of merit, etc.)

→ Investigations of cross-plane and in-plane thermal transports in dependence on thin film thicknesses



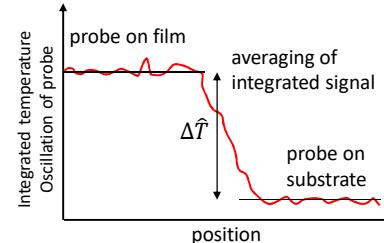
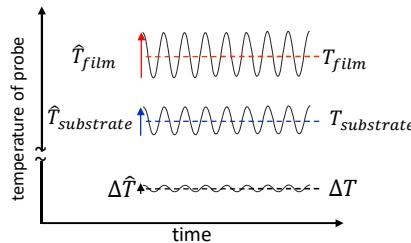
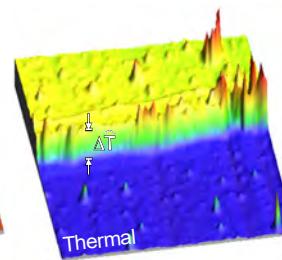
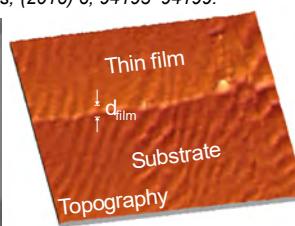
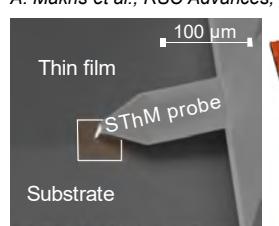
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Scanning Thermal Microscopy on thin films

A. Makris et al., RSC Advances, (2016) 6, 94193–94199.



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Out-of-plane heat transport



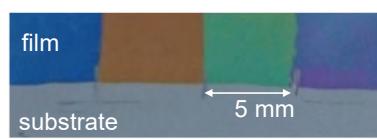
*Si substrate λ_{Si} : 150 Wm⁻¹K⁻¹

Al_2O_3 films $\lambda_{\text{Al}_2\text{O}_3}$: 0.8 Wm⁻¹K⁻¹

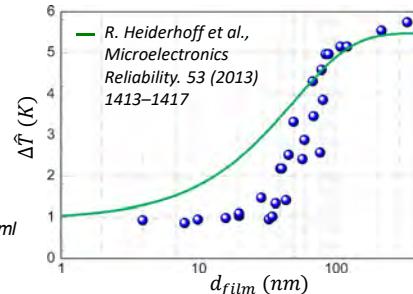
** $\Lambda_{\text{Al}_2\text{O}_3}$: 0.47–3.5 nm

*DETERM, (2017) <http://www.dechema.de/Detherm.html>

**N. Oka et al., Thin Solid Films, (2010) 518, 3119–3121



optical image of fabricated
step-like film matrix



$$\Delta \hat{T}(d_{film} \ll w) = \frac{\hat{P}}{w \cdot \lambda_{film}} \cdot d_{film}, \quad w = 2 \cdot r_{contact}$$

$$\Delta \hat{T}(d_{film}) = \frac{\hat{P}}{\lambda_{film}} \cdot (1 - e^{-\frac{d_{film}}{2r_{contact}}}) + \hat{T}_{contact}$$

⇒ enhanced out-of-plane heat dissipation

***S.-M. Lee and D. G. Cahill, Journal of Applied Physics, (1997) 81, 2590–2595



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Stefan-Boltzmann-like heat transport

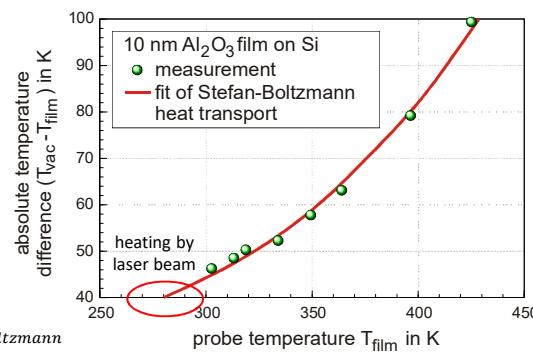
electrical heating $\hat{P}_{electr.} = \dot{Q}_{vacuum}$

$$\dot{Q}_{probe} = \frac{T_{vac} - T_0}{R_{probe}}$$



electrical heating $\dot{Q}_{probe} = \frac{T_{film} - T_0}{R_{probe}}$

$$= \dot{Q}_{vacuum} - \dot{Q}_{Stefan\ Boltzmann}^*$$



$$\frac{T_{vac} - T_{film}}{R_{probe}} = e^{-\frac{d_{film}}{\Lambda_{film}}} \sigma A_{Stefan\ Boltzmann} (T_{film}^4 - T_0^4)$$

σ : Stefan-Boltzmann constant for phonons

Λ_{film} : phonon mean-free path

$A_{Stefan\ Boltzmann}$: effective contact area for ballistic heat transport

*A. Majumdar, Journal of Heat Transfer, (1993) 115, 7–16

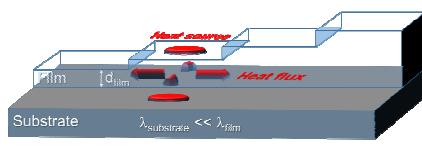


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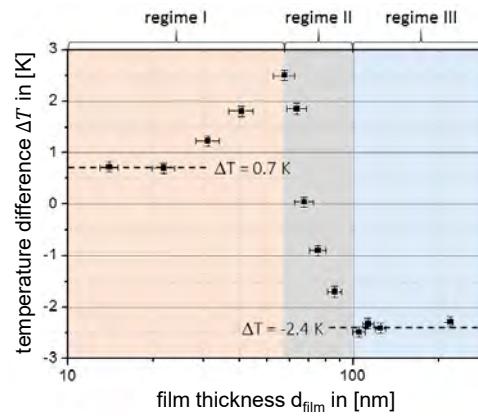
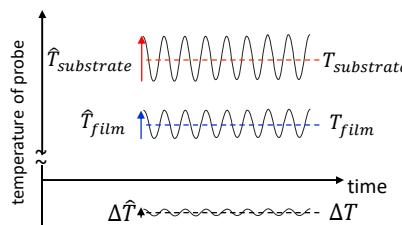
In-plane heat transport



*glass substrate $\lambda_{\text{glass}}: 0.8\text{--}1.4 \text{ Wm}^{-1}\text{K}^{-1}$

** TiO_2 films $\lambda_{\text{TiO}_2}: 2\text{--}8 \text{ Wm}^{-1}\text{K}^{-1}$

*** $\Delta_{\text{TiO}_2}: 0.4\text{--}1 \text{ nm}$



*DETERM, (2017) <http://www.dechema.de/Detherm.html>.

**D.J. Kim et al., Int. J. of Thermophysics, (2004) 25, 281–289.

***C. B. Carter, M. G. Norton, in Ceramic Materials, (2013), 641–657



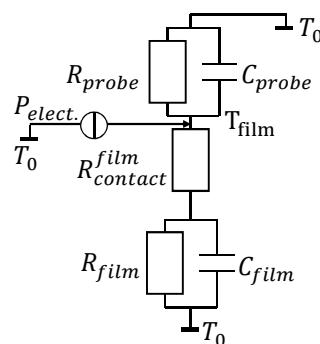
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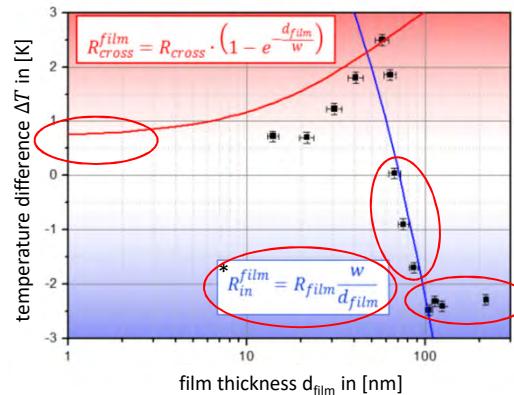


In-plane heat transport

Heiderhoff R. et al., Microelectronics Reliability (2017),
doi: 10.1016/j.microrel.2017.06.064



TiO_2 layer considered as bulk material in case of $d_{\text{film}} > 100 \text{ nm}$



*D. Chu et al. Journal of Vacuum Science & Technology B:
Microelectronics and Nanometer Structures, (2001) 19, 2874

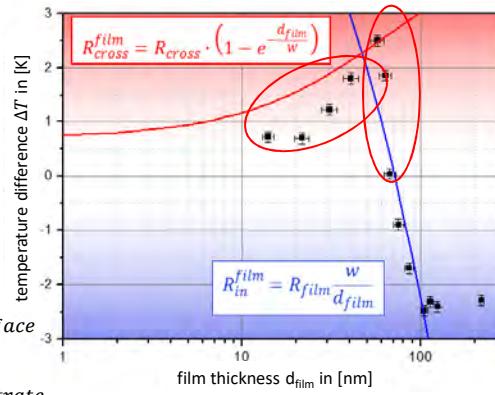
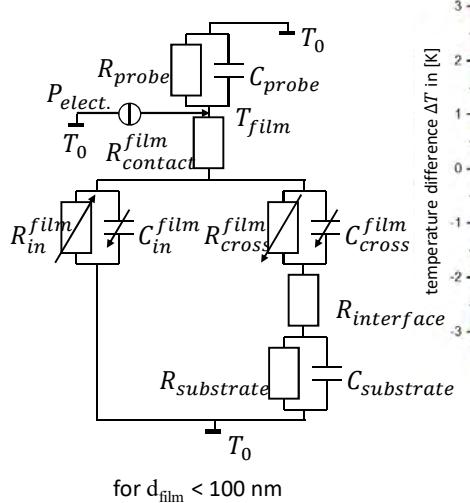


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Disparate anisotropic heat transport



significant reduction of the Boltzmann-like heat flux due to phonon scattering
phonon transport, *Journal of Heat Transfer*,
(2013) 135, doi:10.1115/1.4023577

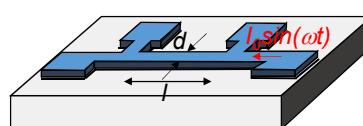


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Frequency dependence of 3ω -method



D. G. Cahill, *Review of Scientific Instruments*, 1990, **61**, 802–808

$$\text{wave number } k = \sqrt{\frac{\omega}{2a}}$$

$$\text{thermal diffusivity: } a = \frac{\lambda}{\rho c}$$

$$1/k \gg d : \omega_{\max} \ll 2a/d^2$$

$$1/k < l : \omega_{\min} > 2a/l^2$$

temperature distribution of line heat source with thermal penetration depth $\frac{1}{\alpha}$ (approximation):

$$\hat{T} = \frac{\hat{P}}{l \cdot \pi \cdot \lambda} \cdot J_0(\sqrt{j\alpha r}) = \frac{\hat{P}}{l \cdot \pi \cdot \lambda} \cdot \underbrace{\left(\ln(2) - 0.5772 - \frac{j\pi}{4} + \frac{1}{2} \ln\left(\frac{a}{r^2}\right) - \frac{1}{2} \ln(\omega) \right)}_{\text{quantities to be insert in SI without units!}}$$

analysis in the frequency domain

$$\frac{\hat{U}_{3\omega_1} - \hat{U}_{3\omega_2}}{\ln(\omega_1) - \ln(\omega_2)} = \frac{\hat{P}}{l \cdot \pi \cdot \lambda} \cdot \frac{1}{4} I_0 \cdot \frac{dR}{dT}$$



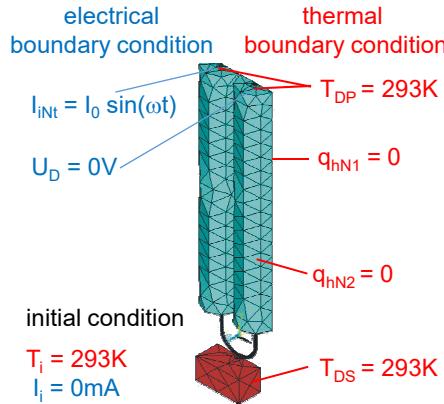
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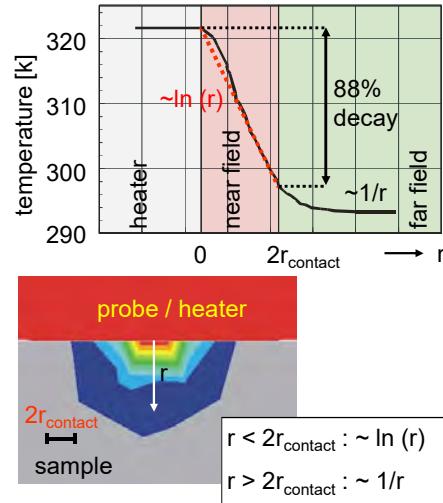


Validation of 3ω -method

FEM model of thermal probe:



Altes A. et al.: *Journal of Physics D: Applied Physics*, 37 (2004), issue 6, pp 952 - 963



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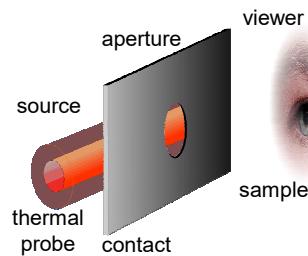


Validation of 3ω -method

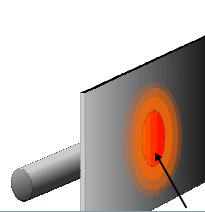
Near field condition of thermal probe:

Altes A. et al.: *Journal of Physics D: Applied Physics*, 37 (2004), issue 6, pp 952 - 963

New approach of estimation



Conventional estimation



temperature distribution and frequencies depend on probe characteristic

I. S. Gomès et al., *Phys. Status Solidi A* **212**, No. 3, 471

Heiderhoff R. and Balk L.J.,
*"Scanning Probe Microscopy-History,
 Background, and State of the Art",
 in Handbook of Nanoscopy (Wiley)
 2012*



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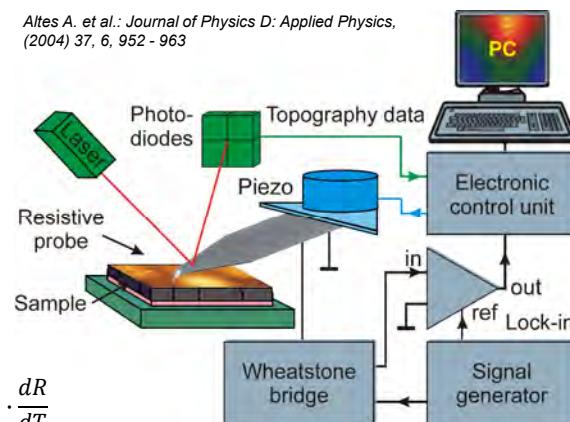
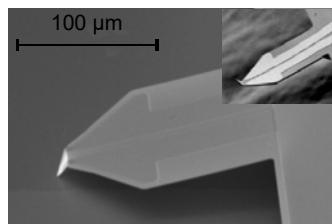
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Set-up of Scanning Thermal Microscope

P. Tovee et al.: *Journal of Applied Physics*, (2012) 112, 114317

Altes A. et al.: *Journal of Physics D: Applied Physics*, (2004) 37, 6, 952 - 963



$$\frac{\hat{U}_{3\omega_1} - \hat{U}_{3\omega_2}}{\ln(\omega_1) - \ln(\omega_2)} = \frac{\hat{P}}{l \cdot \pi \cdot \lambda} \cdot \frac{1}{4} I_0 \cdot \frac{dR}{dT}$$

D. G. Cahill, *Review of Scientific Instruments*, (1990) 61, 802–808

S. Lefèvre, S. Volz, *Rev. Sci. Instrum.* 76 (2005) 033701
S. Gomès et al., *Phys. Status Solidi A* (2015) 212, 3, 477–494.

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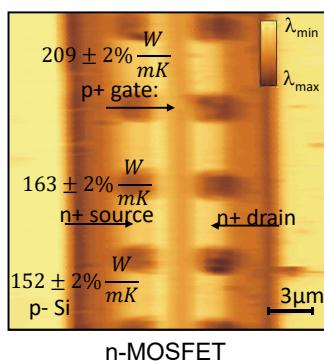
Scanning Thermal Microscopy

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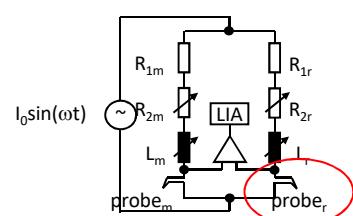
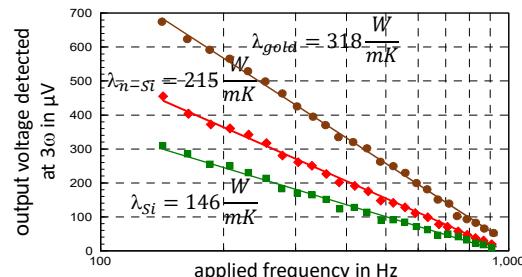
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Quantitative thermal conductivity analysis on doped areas



T.H. Lee et al., 27th Int. Symp. Test. Fail. Anal., 2001: pp. 191–197



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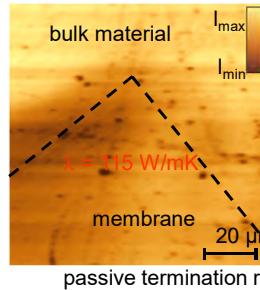
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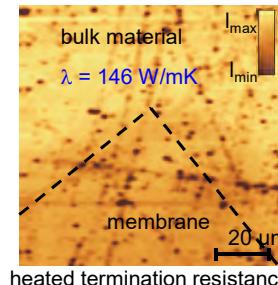
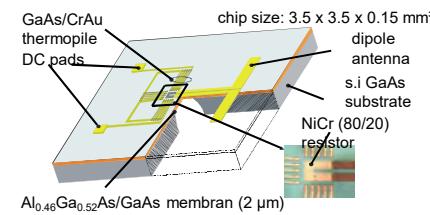
Thermal conductivity distribution on active devices

Local thermal conductivity $\lambda(T)$ analyses on micro-machined thin membrane using 3ω method

Interface
membrane – bulk



A. Altes et al., *Superlattices Microstruct.* 35 (2004) 465–476



heated termination resistance



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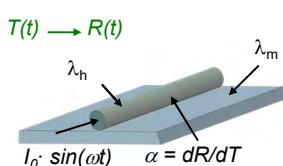
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Frequency domain of Scanning Thermal Microscopy

Electrical 3ω -signal generation:

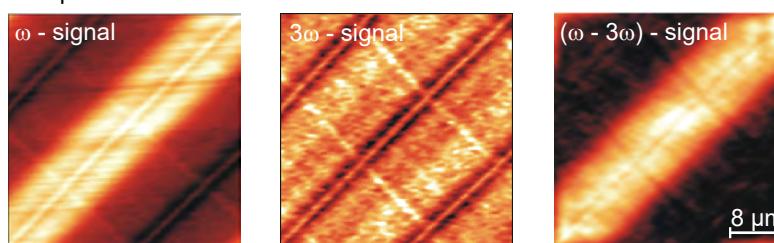
D. G. Cahill, *Review of Scientific Instruments*, 1990, **61**, 802–808



$$R(t) = R_0 - dR/dT \cdot \hat{T}/2 \cdot \cos(2\omega t - \varphi)$$

$$U(t) = I_0 \cdot R_0 \cdot \sin(\omega t) + I_0 \cdot \hat{T}/4 \cdot dR/dT \cdot \sin(\omega t - \varphi) \\ - I_0 \cdot \hat{T}/4 \cdot dR/dT \cdot \sin(3\omega t - \varphi)$$

Removal of conductivity information and impact of tip–sample thermal resistance from temperature measurements



see also: A. Reihani et al., *ACS Nano*, 2021, doi:10.1021/acsnano.1c08513



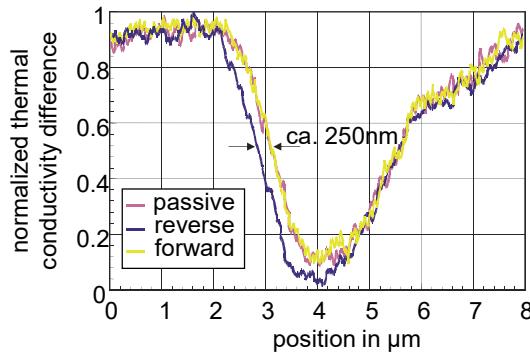
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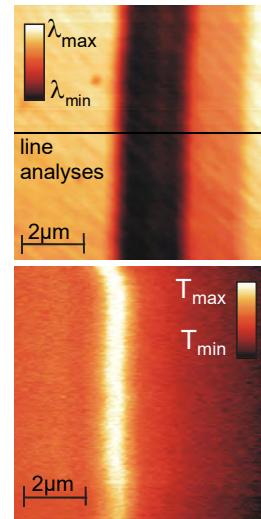


Scanning Thermal Microscopy on active devices

Local thermal conductivity analyses on a InGaAlP-LED under different biasing conditions:



R. Heiderhoff et al., J. Phys. Low Dimens. Struct. 1/2 (2004) 63–70

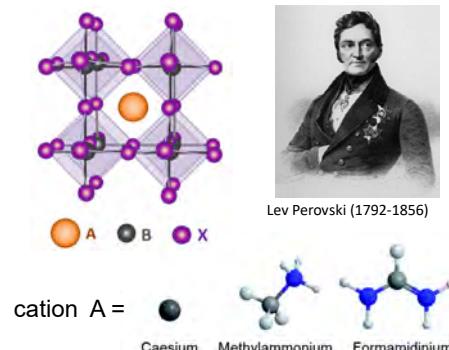


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Motivation and Purpose

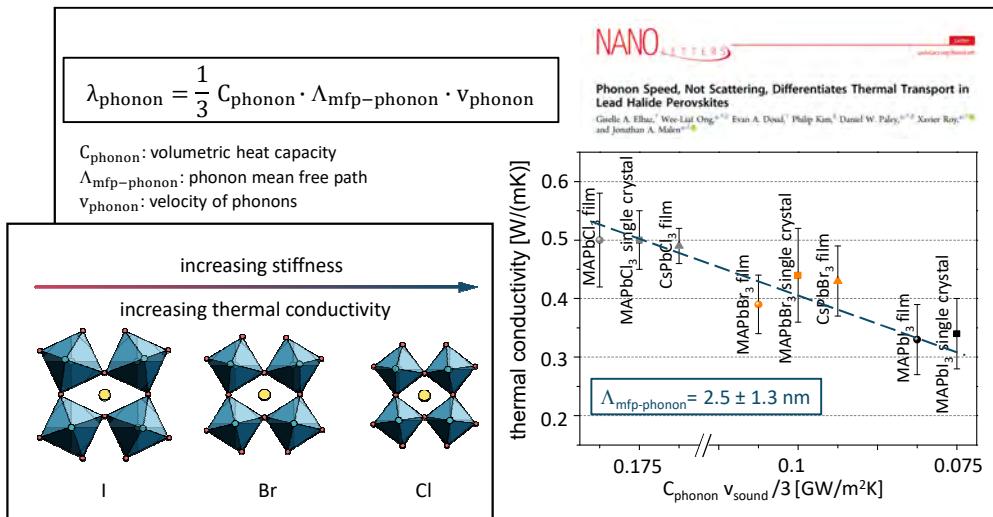


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Thermal conductivity of halide perovskites



Haeger T. et al., J. Mater. Chem. C, (2020), DOI: 10.1039/D0TC03754K

& improved air-stability



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Quantitative thermal conductivity mapping

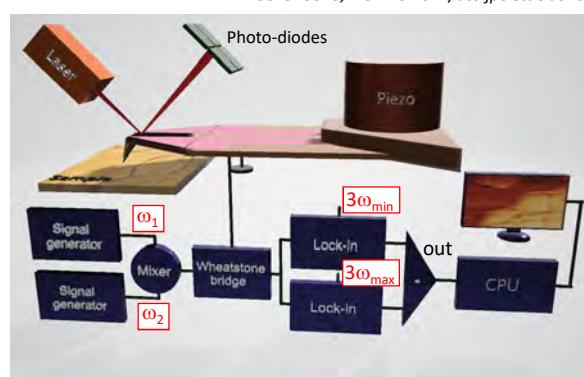
Haeger T. et al., J. Phys. Chem. Lett. (2019), 10, 3019–3023, DOI: 10.1021/acs.jpclett.9b01053

$$\frac{\hat{U}_{3\omega_1} - \hat{U}_{3\omega_2}}{\ln(\omega_1) - \ln(\omega_2)} = \frac{\hat{P}}{l \cdot \pi \cdot \lambda} \cdot \frac{1}{4} I_0 \cdot \frac{dR}{dT}$$

applying mixed voltage signal:

$$U(t)_{\text{bridge}} = \frac{1}{c} U_a \sin(\omega_a t + \varphi_a) + U_b \sin(\omega_b t + \varphi_b)$$

c: coupling factor [V]



signal: phase neglected

$$U(t)_{\text{probe}} = (I_0 R_0 - I_0 \frac{dR}{dT} \cdot \frac{\hat{T}}{4}) (\cos(\omega_1 t) + \cos(\omega_2 t)) + I_0 \frac{dR}{dT} \cdot \frac{\hat{T}}{4} (\cos(3\omega_1 t) + \cos(3\omega_2 t))$$

$$= I_0 \frac{dR}{dT} \cdot \frac{\hat{T}}{4} (\cos((2\omega_1 - \omega_2)t) - \cos((2\omega_1 + \omega_2)t) - \cos(2\omega_2 - \omega_1)t + \cos(2\omega_2 + \omega_1)t)$$

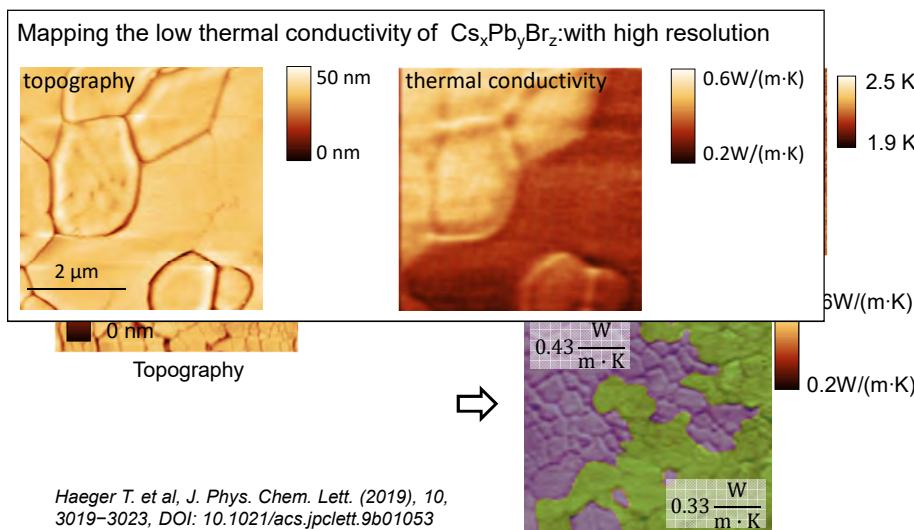


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Quantitative thermal conductivity mapping

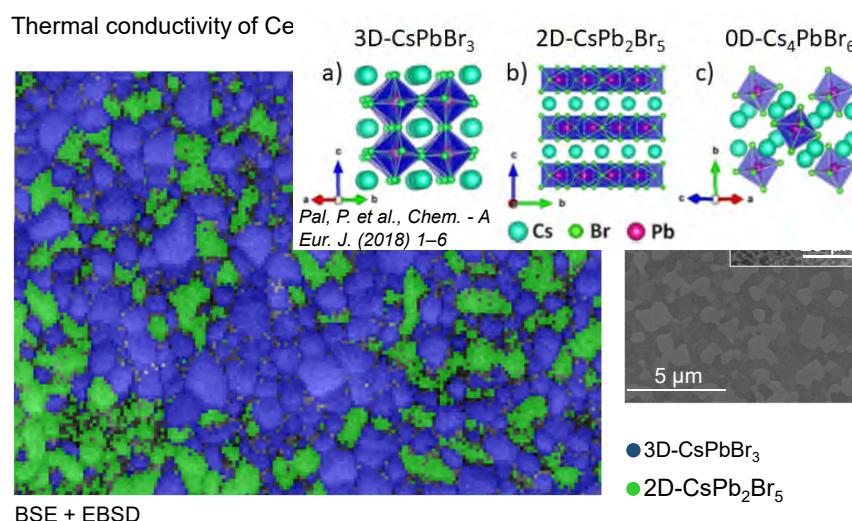


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Quantitative thermal conductivity mapping

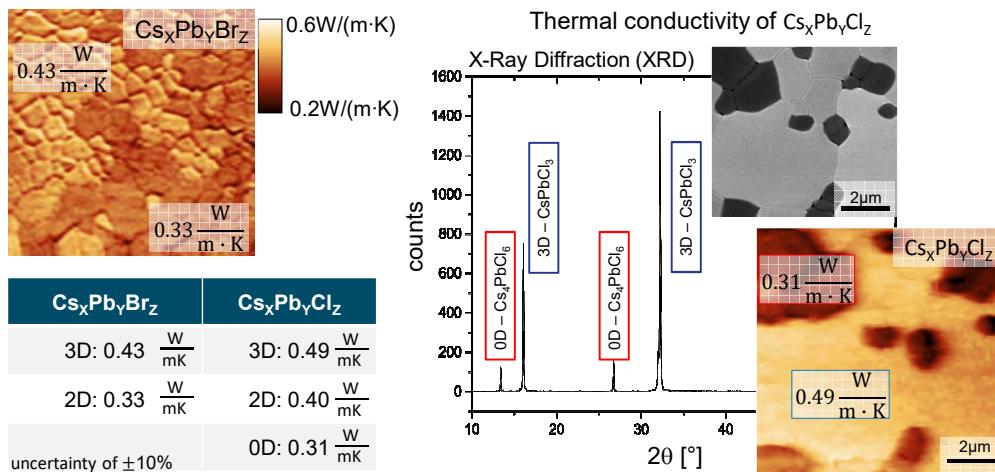


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Quantitative thermal conductivity mapping



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Simultaneous Mapping of Thermal Conductivity, Thermal Diffusivity, and Volumetric Heat Capacity

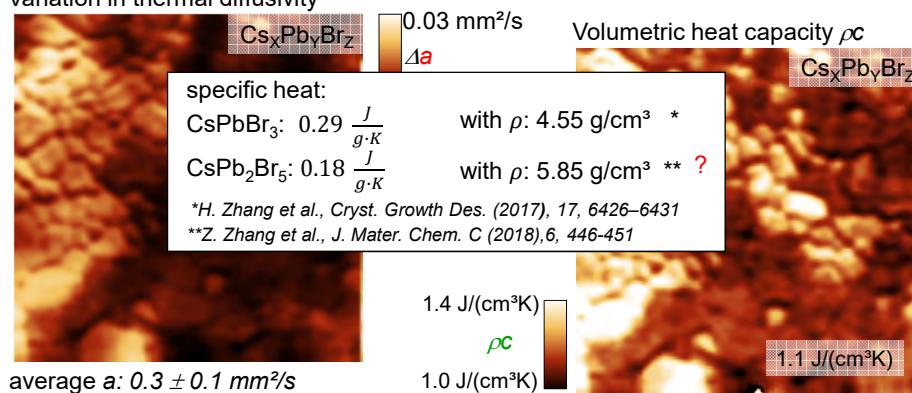
Haeger T. et al, J. Phys. Chem. Lett. (2019), 10, 3019–3023, DOI: 10.1021/acs.jpclett.9b01053

$$\hat{T} = \frac{\dot{Q}_s}{\lambda} \cdot \left(\frac{1}{2} \ln \left(\frac{a}{r^2} \right) - \frac{1}{2} \ln(\omega) + \ln(2) - 0.5772 - \frac{j\pi}{4} \right) \quad \frac{\partial T(\vec{x}, t)}{\partial t} = a \cdot \Delta T(\vec{x}, t)$$

D. G. Cahill, Review of Scientific Instruments, 1990, 61, 802–808

$$[\dot{Q}_s] = \frac{\text{W}}{\text{m}}$$

Variation in thermal diffusivity



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Simultaneous Mapping of Thermal Conductivity, Thermal Diffusivity, and Volumetric Heat Capacity

Haege T. et al., J. Phys. Chem. Lett. (2019), 10, 3019–3023, DOI: 10.1021/acs.jpclett.9b01053

$$\hat{T} = \frac{\dot{Q}_s}{\lambda} \cdot \left(\frac{1}{2} \ln \left(\frac{a}{r^2} \right) - \frac{1}{2} \ln(\omega) + \ln(2) - 0.5772 - \frac{j\pi}{4} \right) \quad \frac{\partial T(\vec{x}, t)}{\partial t} = a \cdot \Delta T(\vec{x}, t)$$

D. C.

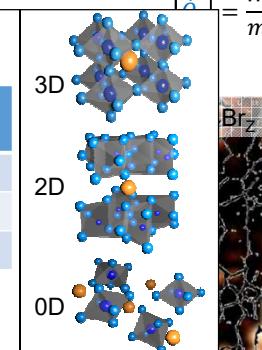
Var

Thermal properties of Cs based chloride perovskites

perovskite	λ [W/(mK)]	a [mm ² /s]	c_v [J/(cm ³ K)]
3D-CsPbCl ₃	0.53	0.5	1.1
2D-CsPb ₂ Cl ₅	0.40	0.6	0.7
0D-Cs ₄ PbCl ₆	0.30	0.5	0.5

T. Haege et al., in MRS Fall Meeting, Boston, 2019, p. EN09.15.02

T. Haege et al., J. Phys. Mater., 2020, 3, 024004

average a: $0.3 \pm 0.1 \text{ mm}^2/\text{s}$ $\Delta\rho c$ 0 J/(cm³K)

W/m



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Motivation and Purpose

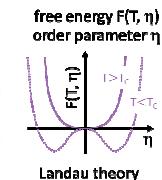
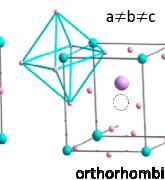
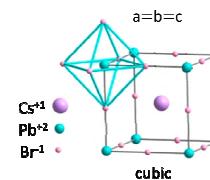
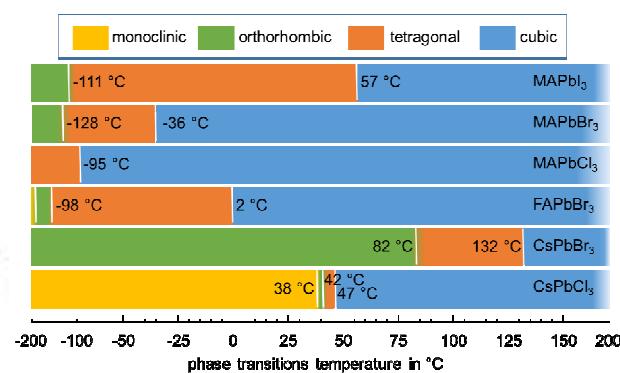
Phase transitions of
halide perovskites

T. Haege et al., J.Mater.Chem.C,
2020, 8, 14289-14311

Adv. Mater., 2016, 28,
6804–6834

Perovskite Materials for Light-Emitting Diodes and Lasers

Sjoerd A. Vrijdaghs, Pablo P. Boix,¹ Natalia Yantara, Mingjie Li, Tze Chien Sum,
Ningan Mothiram, and Subodh C. Manoharan^{2*}

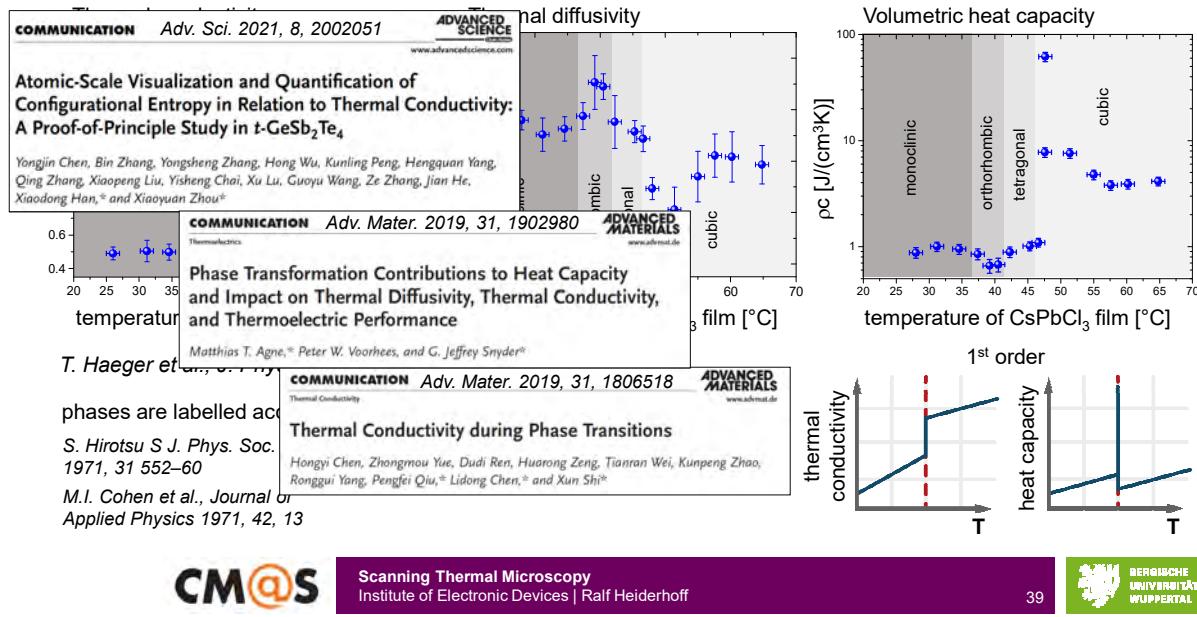


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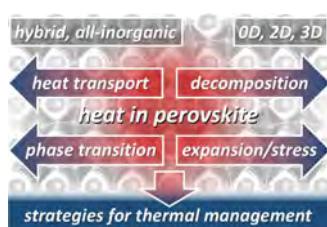
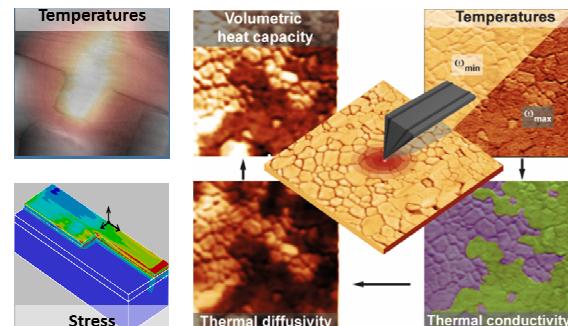
Thermal properties of CsPbCl_3 at phase transitions



Closing remarks

- Thermal and thermoelastic quantities determinable
- on ultra-high und ultra-low thermal conductors
 - with spatial resolution in the nanometer range
 - with femto-meter sensitivity
 - on thin films
 - at phase transitions

Scanning near-field thermal microscopy techniques assisted by complementary finite element simulation



- Reliability investigations on smart materials and devices
- Transition from diffusive heat flux to ballistic Stefan–Boltzmann like heat transport in thin films
- Thermal properties of hybrid and all-inorganic perovskites in dependence on choice of cations & halides, dimensionality, and crystal-phase
 - ultra low thermal conductivities
 - low thermal diffusivities
 - low volumetric heat capacities



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Thank you for your attention



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